

Abstract

Method for fabricating a trench isolation structure

5 The invention provides a method for fabricating a trench  
isolation structure, comprising the following steps:  
forming a mask (3) on a substrate (1); forming at least  
one trench (2) in the substrate (1) by means of the mask  
(3); carrying out selective deposition of a first  
10 insulation material (5) to at least partially fill the at  
least one trench (2) in the substrate (1) with the  
insulation material (5) in the presence of the mask (3);  
and applying a second insulation material (6) over the  
entire surface of the structure in order to fill the at  
15 least one trench (2) in the substrate (1) at least up to  
the top side of the mask (3).

Fig. 3